Oxidation Resistance of Iron and Copper Foils Coated with Reduced Graphene Oxide Multilayers

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The protection of metal surfaces is important, and many approaches have been developed. Coating with other metal(s), 1 chemical modification, 2 anodizing, 3 using an oxide layer, 4 and organic layer/polymer coating are some examples. 5– 8 Recently, graphene, which was successfully grown on large-area Cu substrates by a chemical vapor deposition (CVD) method, 9 was tested as a barrier and shown to protect Cu and Cu/Ni alloy surfaces from oxidation. 10, 11 Fe, widely used in industry, can also be used for CVD graphene growth. 12, 13 However, to date, uniform graphene layers have not been achieved on Fe substrates. 14 Reduced graphene oxide (rG-O), when deposited as a thin film, is an alternative candidate for protecting Fe and Cu surfaces because large thin films can be readily formed by a solution process. 15 Furthermore, rG-O can be easily synthesized in a large quantity by oxidation of natural graphite, followed by reduction with a wide variety of reducing (deoxygenating) agents or by thermal treatment. 16

rG-O has been used in organic thin-film transistors (OTFTs) and field-effect transistors (FETs), 17, 18 conducting transparent films, 15, 19– 24 sensors, 25, 26 and energy storage materials, 27 but oxidation resistance of rG-O-coated metal surfaces to our knowledge has not been reported. We expected that rG-O multilayers might act as a diffusion barrier to gas molecules (including oxidants such as H₂O and O₂) and thus as a protective layer to prevent or slow oxidation in metals.

Herein semitransparent rG-O multilayers were fabricated on a SiO₂ (300 nm) deposited on Si substrate by layer-by-layer (LBL) assembly of negative and positive charged graphene oxide sheets, followed by thermal treatment. 28, 29 The rG-O thin films were then transferred onto Fe and Cu foils to assess the oxidation resistance of these rG-O-coated metal surfaces. The possible oxidation of bare metal and rG-O-coated metal surfaces was investigated by Raman spectroscopy, optical microscopy, and scanning electron microscopy after heat treatment at 200 °C in air for 2 h. The bare metal surfaces were severely oxidized, but the rG-O-coated metal surfaces were protected from oxidation. This simple solution process using rG-O is one advantage of the present study.

KEYWORDS: graphene oxide · reduced graphene oxide · iron · oxidation resistance · gas barrier

ABSTRACT

Protecting the surface of metals such as Fe and Cu from oxidizing is of great importance due to their widespread use. Here, oxidation resistance of Fe and Cu foils was achieved by coating them with reduced graphene oxide (rG-O) sheets. The rG-O-coated Fe and Cu foils were prepared by transferring rG-O multilayers from a SiO₂ substrate onto them. The oxidation resistance of these rG-O-coated metal foils was investigated by Raman spectroscopy, optical microscopy, and scanning electron microscopy after heat treatment at 200 °C in air for 2 h. The bare metal surfaces were severely oxidized, but the rG-O-coated metal surfaces were protected from oxidation. This simple solution process using rG-O is one advantage of the present study.

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and also the thickness of rG-O multilayers are factors affecting the degree of protection against oxidation of the metal surface. We concluded that the optimized condition for effective protection of the Fe or Cu surfaces from oxidation is five bilayers of rG-O and heat treatment above 800 °C for a suitable time as discussed further below. The advantage of using rG-O multilayers is that they are deposited by a solution process that is easy, reproducible, and transferrable to any substrate.

RESULTS AND DISCUSSION

Graphene oxide (G-O) suspensions were prepared by exfoliation of graphite oxide synthesized by the modified Hummers method.30 The G-O sheets had an average lateral size of 8.34 μm and typical thickness of 0.8−1.0 nm, indicating that the majority of the sheets in the sample were single-layer (Figure S1 in the Supporting Information). The G-O suspension had good colloidal stability with a zeta-potential of less than −50 mV over a wide range of pH (Figure S2a in the Supporting Information). Negatively charged G-O sheets were converted into positively charged G-O sheets by reaction between the carboxylic acid groups of G-O and ethylenediamine mediated with N-ethyl-N′-(3-dimethylaminopropyl)carbodiimide methiodide;29 the pH of the solution was adjusted to 3 to 4 with 0.1 M HCl. A well-dispersed and stable solution of positively charged G-O sheets was then obtained without agglomeration at a concentration of ~0.4 mg/mL; the zeta potential was 50.2 mV at pH 3.7 (Figure S2a in the Supporting Information).

rG-O thin films on Si wafer substrates having a 300 nm thick thermal oxide layer were fabricated by repetitively spin-coating first the positively and then the negatively charged G-O solutions (LbL assembly) and thermal treatment. The LbL assembly allows for precise control of the thickness of the G-O thin films through the number of bilayers (see Figure S2b in the Supporting Information). The thickness of the rG-O thin films after thermal treatment was smaller than that of the G-O thin films. The decrease in thickness of the rG-O thin films was due to several factors, including removal of O-containing functional groups by heating and elimination of interlamellar water that was present in both graphite oxide and G-O thin films and that depended on relative humidity. The X-ray photoelectron spectroscopy (XPS) data (Figure S2c in the Supporting Information) show the extensive reduction in O-containing functional groups as a function of the temperature used for the deoxygenation. From the deconvolution of C 1s peaks in the XPS spectra, it was observed that C−O and C=O peaks at 286.8 and 288.5 eV dramatically decreased after the thermal reduction at 1100 °C, whereas the C=C peak at 284.8 eV increased (see deconvoluted C1s peaks of G-O and rG-O in Figure S2 in the Supporting Information.) Furthermore, the peak at 284.8 eV shifted to 284.4 eV as the temperature increased to 1100 °C. These results are in good agreement with previous literature.29,31 The 8.8 nm thickness for five-bilayer G-O decreased to 3.3 nm after heating at 1100 °C for 1 h under vacuum (Ar 90 sccm and H2 10 sccm). It is also interesting that the interlayer spacing of the rG-O thin film after thermal treatment was very similar to that of crystalline graphite (see XRD data in Figure S3), and surface morphology became smooth after thermal treatment.
(see AFM data in Figure S4). Of course, crystallinity of the rG-O thin film is worse than graphite. This indicates that rG-O layers were well packed with removal of O-containing functional groups by thermal treatment at 1100 °C.

The rG-O thin films could also be obtained by reduction of the G-O thin films by hydrazine vapor at 100 °C, and hydrazine molecules and some N-functionalized groups remained in the rG-O multilayers (Figure S5 in the Supporting Information). The rG-O thin films obtained by exposure to hydrazine vapor were found to not protect Fe or Cu foil surfaces, and this is likely due to residual hydrazine molecules and defect sites (Figure S5). We thus focus discussion on the rG-O thin films prepared by thermal reduction as protective layers.

The scheme for the preparation of rG-O-coated metals and photographs of the five-bilayer rG-O-coated Fe and Cu foils before and after oxidation are shown in Figure 1. The oxidation of Fe and Cu foils was done by heating them at 200 °C in air for 2 h. Apparently, it seems that the rG-O layers protect oxidation of Fe and Cu foils. (Evidence of the oxidation resistance will be provided using Raman spectroscopy, optical microscopy, and SEM later.) The rG-O layers were obtained by thermal reduction at 1100 °C as demonstrated above.

Raman spectra of rG-O-coated Fe foils before and after oxidation were measured to assess oxidation resistance. The rG-O-coated Fe foils were prepared at various reduction temperatures from 200 to 1100 °C. It is noted that a red shift of the G band was observed from 1602 to 1585 cm⁻¹ as the reduction temperature increased (Figure 2a). Generally, a restored sp²-hybridized graphitic carbon network by reduction at...
high temperature can lead to a shift of the G band,\(^{32}\) which is consistent with our XPS data (Figure S2d in the Supporting Information). It is particularly noteworthy that various Raman bands due to iron oxide phases such as FeOOH (218, 285, 289, and 397 cm\(^{-1}\)), Fe\(_2\)O\(_3\) (406, 657, and 670 cm\(^{-1}\)), and Fe\(_3\)O\(_4\) (603 and 670 cm\(^{-1}\))\(^{33,34}\) appeared in the spectral region of 100 and 800 cm\(^{-1}\) after oxidation of rG-O-coated Fe samples reduced at temperatures below 800 °C. On the other hand, there was no Raman band due to iron oxide phases after oxidation of rG-O-coated Fe samples reduced at 800 and 1100 °C (Figure 2b). Note that a very weak band at 670 cm\(^{-1}\) was due to native iron oxide on Fe foil and appeared even in Raman spectra before oxidation in Figure 2a and in the Raman spectrum of bare Fe foil in Figure S11. From Raman spectra in Figure 2b, the degree of oxidation of rG-O-coated Fe samples was investigated by calculating the Raman intensity ratio of a band at 397 cm\(^{-1}\) due to α-FeOOH (goethite: a kind of iron oxide) and the G band as an internal standard. Figure 2c shows the ratio \(I_{\text{FeOOH}}/I_G\) at different temperatures. The \(I_{\text{FeOOH}}/I_G\) values gradually decreased as the reduction temperature increased (1.83 at 200 °C, 0.99 at 400 °C, and 0.29 at 600 °C) and finally approached zero at 800 and 1100 °C. This result indicates that rG-O-coated Fe foils reduced at low temperature were heavily oxidized, whereas those at 800 and 1100 °C were protected from oxidation. Figure 2d shows thickness changes of the rG-O thin films as a function of the thermal reduction temperature. It is interesting that the thickness of the rG-O thin films decreased with an increase of the reduction temperature, which is the same tendency as the change of the intensity ratio in Figure 2c. The thicker films reduced at temperatures of 200 to 600 °C were due to existing functional groups in the rG-O layers, which were not completely removed by the thermal treatment, so water and oxygen could permeate through the thick films. It appears that the partially reduced G-O films did not play a role as a diffusion barrier of gas and did not protect the Fe surface from oxidation. Furthermore, the existing functional groups containing oxygen may accelerate oxidation of the Fe surface. On the other hand, the rG-O thin films reduced at 800 and 1100 °C are supposed to be well packed without functional groups (see XRD data in Figure S3) and so play a role as a barrier of gas (see Figure S6 in the Supporting Information for measurement of He gas permeability). It is known that water molecules permeate G-O membranes of 1 μm thickness but not a 1 μm thick rG-O membrane, whereas He gas does not permeate either 1 μm thick G-O or rG-O membranes.\(^{35}\) However, it is difficult to compare these prior results with the rG-O multilayers films studied here, as they are very thin, less than 10 nm. We made attempts to measure the permeability to He gas but our thin rG-O films broke during attempts to mount them. The contact angle measurement in Figure 2e supports the existence of functional groups between 200 and 600 °C. The contact angle was 54° for G-O, 78° at 200 °C, 82° at 400 °C, 83° at 600 °C, 87° at 800 °C, and 88° at 1100 °C. As the temperature increased, the contact angle increased, indicating removal of oxygen-containing functional groups.\(^{36,37}\)

The oxidation resistance of the rG-O layer was also confirmed by optical microscopy (OM) and SEM. Figure 3a–d show OM images of bare Fe and five-bilayer rG-O-coated Fe before and after oxidation. The color of the bare Fe changed to brown after oxidation, whereas the color of the rG-O-coated Fe remained unchanged after oxidation. Note that the color of the rG-O-coated Fe was slightly darker than that of the bare Fe due to the rG-O layer. SEM images also showed a noticeable difference between the bare Fe and the rG-O-coated Fe after oxidation. The bare Fe shows morphology of particulates after oxidation in Figure 3g, whereas the rG-O-coated Fe remains without a morphology change in Figure 3h. rG-O multilayers of one and three bilayers...
were ineffective as a gas barrier for oxidation resistance of metal possibly due to poor coverage. Among thicker rG-O films of 10, 15, and 20 bilayers, rG-O films of 15 and 20 bilayers were also ineffective as a gas barrier for oxidation resistance of Fe (see Figures S7–S10 in the Supporting Information). Thus, we reach a conclusion that five bilayers in rG-O multilayers is either the optimum or close to the optimum thickness for oxidation resistance and optical transparency: the five-bilayer film is more transparent than a 10-bilayer-thick film.

The oxidation resistance of the rG-O layer can be applied to Cu foil. The preparation method of the rG-O layer and the oxidation procedure for Cu foil were identical to those for Fe foil. Figure 4a–d show photographs and OM images of bare Cu and rG-O-coated Cu. The color of the bare Cu turned greenish after oxidation, whereas the color of the rG-O-coated Cu remained unchanged. Note that the color of the rG-O-coated Cu is slightly darker than that of the bare Cu.

The comparison of Raman spectra before and after oxidation in Figure 4e, f also revealed that the rG-O layer successfully protected the Cu surface. The Raman spectrum of the bare Cu after oxidation shows some bands due to copper oxides such as Cu2O (219 cm\(^{-1}\)) and CuO (287, 329, and 619 cm\(^{-1}\)).\(^{38,39}\) On the other hand, the Raman spectrum of the rG-O-coated Cu after oxidation did not show any band in the spectral region. Note that two large Raman bands between 1250 and 1700 cm\(^{-1}\) are called D and G bands and originated from the rG-O layer.

CONCLUSIONS

The rG-O multilayers using layer-by-layer assembly were successfully fabricated and transferred to Fe and Cu foils. The oxidation resistance of Fe and Cu foils by the rG-O layers was confirmed by Raman spectroscopy, optical microscopy, and SEM. The results mean that the rG-O layers play a role as a diffusion barrier of gas. The solution process using rG-O is easy and reproducible.

METHODS

Preparation of Graphene Oxide (G-O). Graphite oxide was prepared from purified natural graphite (SP-1, Bay Carbon) using the modified Hummers’ method. The graphite powder (2.0 g) was put into an 80 °C solution of concentrated H\(_2\)SO\(_4\) (3.0 mL), K\(_2\)S\(_2\)O\(_8\) (1.0 g), and P\(_2\)O\(_5\) (1.0 g). The resultant dark blue mixture was thermally isolated and allowed to cool to room temperature over a period of 6 h. The mixture was then carefully diluted with distilled water, filtered, and washed on the filter until the pH of the rinsewater became neutral. The product was dried in air at ambient temperature overnight. This preoxidized graphite was then subjected to oxidation by the Hummers’ method. The preoxidized graphite powder (2.0 g) was put into cold concentrated H\(_2\)SO\(_4\) (46 mL). KMnO\(_4\) (6.0 g) was added gradually with
stirring and cooling, and the temperature of the mixture was not allowed to reach 20 °C. The mixture was then stirred at 35 °C for 2 h, and distilled water (92 mL) was added. After 15 min, the reaction was terminated by the addition of a large amount of distilled water (280 mL) and a 30% H2O2 solution (5.0 mL) after which the color of the mixture changed to bright yellow. The mixture was filtered and washed with a 1:10 HCl solution (500 mL) in order to remove metal ions. The graphite oxide product was suspended in distilled water to give a viscous, brown dispersion, which was subjected to dialysis to completely remove metal ions and acids. Exfoliation of the above graphite oxide to graphene oxide was carried out by dilution of the concentrated graphite oxide dispersion (3.5 mL) with deionized water (35 mL), followed by vigorous stirring at 15 000 rpm with a homogenizer for 15 min and ultrasonication for 10 min. The resulting homogeneous yellow-brown solution, of which the concentration is 0.5 mg/mL, was stable for at least a few months.

Preparation of Positively Charged G-O. Positively charged G-O was synthesized using N-ethyl-N′-(3-dimethylamino propyl)-carbodiimide methiodide (EDC, 98%, Alfa Aesar) and ethylenediamine (99%, Sigma-Aldrich).29 First, concentrated graphite oxide solution (10 mL) was diluted and dispersed in deionized water by ultrasonication treatment for 30 min. Then, 50 mL of G-O suspension (0.5 mg/mL) was combined with EDC (600 mg) and ethylenediamine (4 mL) and stirred for 4 h, and afterward the mixture solution was dialyzed for 24 h to remove EDC and ethylenediamine. The MWCO of the dialysis tubing (Spectra/Por dialysis membrane) was 12 – 14 K. Then the positively charged, dark brown G-O suspension was obtained.

Fabrication of G-O Thin Films Using a Layer-by-Layer Assembly. SiO2 of 300 nm deposited on a Si substrate was cleaned by acetone with ultrasonication to remove any organic contamination and treated by oxygen plasma to introduce a hydrophilic surface. A positively charged G-O solution (5.5 mg/mL) at pH 3.7 was dropped on the 300 nm SiO2 deposited on a Si substrate, which was loaded in a spin coater (ACE-200, Dong Ah Tech), maintained for 60 s as a waiting period, and spun at 3000 rpm for 60 s. As a rinsing step, DI water at the same pH was dropped on the substrate coated with positively charged G-O, maintained for 60 s, and spun at 3000 rpm for 60 s. Next, a negatively charged G-O solution (0.5 mg/mL) at pH 10 was spin-coated with the same procedures, followed by the rinsing step. Then, we obtained one bilayer of G-O sheets. These processes for one bilayer were repeated to make five, seven, or nine bilayers. While the thermal reduction of G-O to make rG-O was generally done at temperatures of 200 – 1100 °C, the G-O samples were maintained at that temperature for 1 h and then slowly cooled, maintaining the inert conditions with the flow of Ar and H2 gases.

Transfer of the rG-O Thin Film to the Metal Surface. The fabricated rG-O thin film on 300 nm SiO2 deposited on a Si substrate needed to be transferred to Cu or Fe foil to test their ability of oxidation resistance (Figure 1). First of all, the rG-O thin film was supported by poly(methyl methacrylate) (PMMA), which is commonly used as a supporting layer of CVD-grown graphene or rG-O thin films because it is robust and easily removed by acetone after the transfer. In this study, an e-beam resist (AR-P 671.04, ALLRESIST) was used as a PMMA supporting layer and coated by spin-coating at 3000 rpm for 30 s. Then, the PMMA-supported rG-O thin film (PMMA/rG-O) on 300 nm SiO2 deposited on a Si wafer was floated in 5 wt % hydrogen fluoride (HF) solution to detach PMMA/rG-O from the substrate by removing a SiO2 layer. The detached PMMA/rG-O was washed out more than three times to eliminate the residual HF acid molecules in their interlayer and transferred onto Fe or Cu foils. The PMMA/rG-O-coated foils were put into acetone for 1 h to remove the PMMA layers.

Characterization. The average size and morphology of the G-O sheets were measured by SEM (Nanonova 230, FEI) and XPS, and Raman spectra. This material is available free of charge via the Internet at http://pubs.acs.org.

REFERENCES AND NOTES


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Supporting Information Available: Additional characterization data of AFM, SEM, XPS, and Raman spectra. This material is available free of charge via the Internet at http://pubs.acs.org.


